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Si2 Open Modeling Coalition Receives Contribution of Statistical Library Format

AUSTIN, Texas--(BUSINESS WIRE)--In response to a Request For Technology (RFT) issued earlier this year, a statistical library format has been contributed to the Open Modeling Coalition (OMC) of the Silicon Integration Initiative (Si2). This technology is based on current source models. In July 2006 Cadence Design Systems (Nasdaq:CDNS), Magma[®] Design Automation Inc. (Nasdaq:LAVA) and Extreme DA, with support from ARM (LSE:ARM) (Nasdaq:ARMHY), Virage Logic Corporation (Nasdaq:VIRL), and Altos Design Automation, had announced their intention to work together under the OMC to accelerate the creation of a standard statistical analysis library format under the OMC to support next-generation, variation-aware integrated circuit (IC) analysis tools.

"Si2 applauds the collaboration of these industry leaders to develop an open, industry-managed format for the statistical analysis of IC design variability," said Steve Schulz, president and CEO of Si2. "This contribution enables the OMC to build on the Effective Current Source Model (ECSM) library format standard it has developed to support timing, power, and other advanced statistical analyses."

Si2 Open Modeling Coalition Driving Advances in IC Modeling Standards

The OMC was formed in September of 2005 to enable open modeling standards in the semiconductor industry. The OMC working groups are currently focused on the ECSM standard, statistical modeling, library characterization, and dynamic modeling. This new contribution of a statistical library format will be considered for standardization by the OMC working group as an extension to ECSM, making it the most complete modeling standard available for addressing nanometer effects. The completed modeling standard will eliminate the need for designers to support multiple library formats, thereby increasing engineering productivity and shortening time-to-market for complex, integrated ICs.

This statistical library format can accurately model the effects of process and environmental variations on ICs. As a result, designers can achieve maximum IC performance when moving to advanced manufacturing process technologies. Using a statistical approach to timing analysis lets designers unlock the true potential of these smaller process technologies by reducing the inherent "pessimism" of current analysis tools, and allows them to reclaim performance that would have otherwise been left on the table. Industry convergence on a single, open-standard statistical modeling format for variation will make easier the broad deployment of statistical analysis technologies to enable IC design at advanced process geometries.

About Si2

Si2 is an organization of industry-leading semiconductor, systems, EDA, and manufacturing companies focused on improving the way integrated circuits are designed and manufactured in order to speed time-to-market, reduce costs, and meet the challenges of sub-micro design. Si2 is uniquely positioned to enable collaboration through a strong implementation focus driven by its member companies. Si2 focuses on developing practical technology solutions to industry challenges. Si2 represents over 100 companies involved in all parts of the silicon supply chain through the world.

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